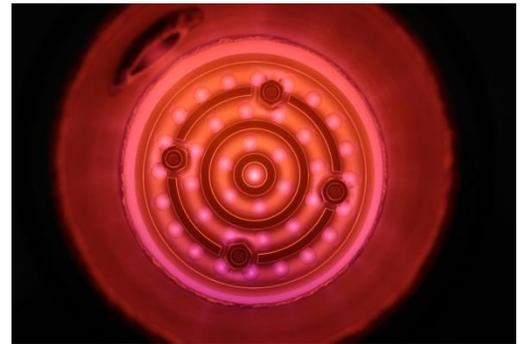




## Large Area Plasma Assisted ALD

As well as ICP replacement sources, Meaglow has developed a range of wider area plasma sources

- Conversion of commercial and home built ALD systems.
- 300 and 600 watt systems , higher power on demand.
- 4" and 8" wafer diametre, plus larger on request.
- 300 watt systems may not require water cooling
- Oxides, nitrides, other
- **Low oxygen contamination** (no dielectrics)
- Cost effective
- High electron density – similar to or greater than inductively coupled and microwave plasma sources, up to  $10^{13}$  cm<sup>-3</sup> for some plasma conditions.
- Wide range of operating pressures (eg. from <50 mTorr to >5 Torr).
- Improved growth per cycle for many material systems



### Related Papers:

- A. Mohammad, et. al., J. Vac. Sci. Technol. **A37** (2019) 020927.
- E. Edri and H. Frei, Journal of Physical Chemistry C **119** (2015) 28326..
- C. Ozgit-Akgun, E. Goldenberg, A. Kemal Okyay and N. Biyikili, Journal of Materials Chemistry C **2** (2014) 2123.

For more information on Meaglow Ltd or its hollow cathode plasma sources, visit our website [www.meaglow.com](http://www.meaglow.com) or contact us at [info@meaglow.com](mailto:info@meaglow.com) .